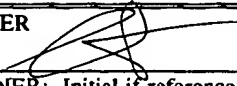


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		29926/39504	To be Assigned
		Applicant	
		10/669 996	
INFORMATION DISCLOSURE STATEMENT		Ju-Il Lee	
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		09/24/03	2813 To be Assigned

U.S. PATENT DOCUMENTS							
*Examiner Initials		Document Number	Issue Date	Name	Class	Subclass	Filing Date if Appropriate

FOREIGN PATENT DOCUMENTS								
*Examiner Initials		Document Number	Publication Date	Country	Class	Subclass	Translation	
							Yes	No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)		
DA		Furumiya et al., <i>High-Sensitivity and No-Crosstalk Pixel Technology for Embedded CMOS Image Sensor</i> , IEEE Transactions on Electron Devices, Vol. 48, No. 10, October 2001, Pages 2221-2227.
DA		Nallapati et al., <i>Influence of Plasma Induced Damage During Active Etch on Silicon Defect Generation</i> , 2000 5 th International Symposium on Plasma Process-Induced Damage, May 23-24, Santa Clara, CA, USA, 2000 American Vacuum Society, Pages 61-64.

EXAMINER	DATE CONSIDERED
	10-26-04
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	